

SILICON-CONTAINING POLYMER, PROCESS FOR ITS PRODUCTION,
RESIST COMPOSITION EMPLOYING IT, PATTERN-FORMING METHOD
AND ELECTRONIC DEVICE FABRICATION METHOD

5

ABSTRACT OF THE DISCLOSURE

10 A silicon-containing polymer having a
tetrafunctional siloxane portion as the basic skeleton,
and containing a carboxylic acid group-containing
triorganosiloxane portion and a carboxylic acid
15 derivative group-containing triorganosiloxane portion in
a specific proportion. It may be advantageously used as
a negative non-chemical amplification resist polymer or a
positive chemical amplification resist polymer.